IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Yia-Chung Chang et al.

Application No.: NEW

Filed: HEREWITH

For: SCATTEROMETRY FOR SAMPLES WITH NON-UNIFORM EDGES

Box Patent Application Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

Group Art Unit: Unknown

Examiner: Unknown

INFORMATION DISCLOSURE STATEMENT

121 Spear Street, Suite 290 San Francisco, CA 94105 (415) 512-1312

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as Express Mail Label No. EV 338307730US in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on March 2, 2004.

STALLMAN & POLLOCK LL

Dated: 03/ 2 /04

Janet Chan

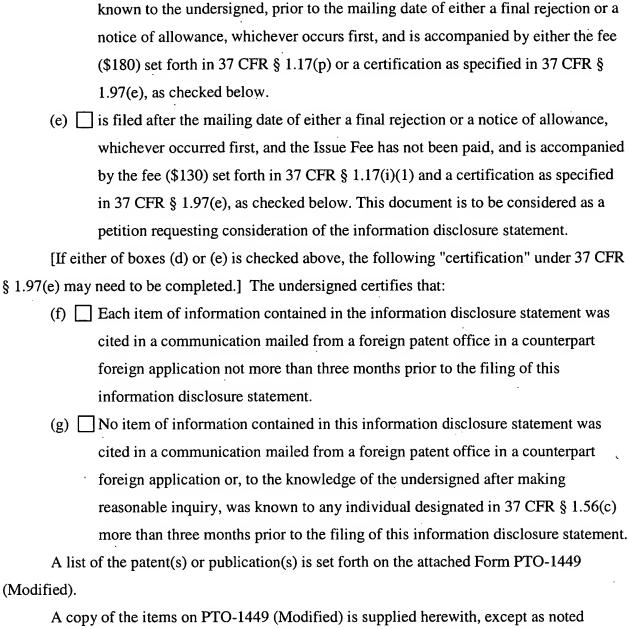
Sir:

Applicant(s) submit(s) herewith patents, publications or other information [attached hereto and listed on the attached Form PTO-1449 (modified)] of which they are aware, which they believe(s) may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

This Information Disclosure Statement:

- (a) accompanies the new patent application submitted herewith. 37 CFR § 1.97(a).
- (b) is filed within three months after the filing date of the application or within three months after the date of entry of the national stage of a PCT application as set forth in 37 CFR § 1.491.
- (c) as far as is known to the undersigned, is filed before the mailing date of a first Office Action on the merits, or before a first office action after filing a Request for Continued Examination under §1.114.
- (d) is filed after the first office action and more than three months after the application's filing date or PCT national stage date of entry filing but, as far as is

Atty Docket No.: TWI-23710



below.

Those patent(s) or publication(s) which are marked with an asterisk (*) in the attached form PTO-1449 (Modified) are not supplied because they are (a) either U.S. Patents and this is an application filed after June 30, 2003, or (b) were previously cited by or submitted to the and relied upon in this application for an Office in a prior application no. , filed earlier filing date under 35 U.S.C. § 120.

A concise explanation of relevance of the items listed on form PTO-1449 (Modified) is:

(k) not given

Atty Docket No.: TWI-23710

(l) given for each listed item				
(m) given for only non-English language listed item(s) [Required]				
(n) is in the form of an English language copy of a Search Report from a foreign				
patent office, issued in a counterpart application, which refers to the relevant				
portions of the references [copy attached].				
The Examiner is reminded that a "concise explanation of the relevance" of the submitted				
items "may be nothing more than identification of the particular figure or paragraph of the patent				
or publication which has some relation to the claimed invention," MPEP § 609.				
While the information and references disclosed in this Information Disclosure Statement				
may be "material" pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that				
any patent, publication or other information referred to therein is "prior art" for this invention				
unless specifically designated as such.				
In accordance with 37 CFR § 1.97(g), the filing of this Information Disclosure Statement				
shall not be construed to mean that a search has been made or that no other material information				
as defined in 37 CFR § 1.56(a) exists. It is submitted that the Information Disclosure Statement				
is in compliance with 37 CFR § 1.98 and MPEP § 609 and the Examiner is respectfully				
requested to consider the listed references.				
The Commissioner is hereby authorized to charge our Deposit Account No. 50-1703,				
under Order No. TWI-23710, for any fees required in connection with the filing of this				
Information Disclosure Statement. A duplicate copy of this Notice is enclosed for this				
purpose. In particular, in the event that an Office Action has crossed in the mail with				
this Information Disclosure Statement, the Commissioner is authorized to charge the				
above-named deposit account for any fees required pursuant to CFR §§ 1.17(p) or				
1.17(i)(1).				
Respectfully submitted,				
STALLMAN & POLLOCK LLP				
Dated: 3/8/04 By: Milw				
Michael A. Stallman Reg. No. 29,444				
Attorneys for Applicant(s)				

Atty Docket No.: TWI-23710

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional) TWI-23710	Application Number NEW		
Applicant(s) Yia-Chung Chang et al.			
Filing Date	Group Art Unit		
HEREWITH	Unknown		

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	Name	CLASS	SUBCLASS	FILING DATE
	*AA	5,607,800	03/04/97	Ziger	430	8	02/15/95
	*AB	5,739,909	04/14/98	Blayo et al.	356	369	10/10/95
	*AC	5,867,276	02/02/99	McNeil et al.	356	445	03/07/97
	*AD	5,889,593	03/30/99	Bareket	356	445	02/26/97
	*AE	5,910,842	06/08/99	Piwonka-Corle et al.	356	369	11/27/96
	*AF	5,963,329	10/05/99	Conrad et al.	356	372	10/31/97
	*AG	6,268,916	07/31/01	Lee et al.	356	369	05/11/99
•	*AH	6,429,943	08/06/02	Opsal et al.	356	625	03/27/01
	*AI	6,483,580	11/19/02	Xu et al.	356	300	03/06/98
	*AJ	2001/0051856	12/13/01	Niu et al.	702	57	01/17/01
	*AK	2002/0158193	10/31/02	Sezginer et al.	250	237	02/12/02
	*AL	2003/0147086	08/07/03	Rosencwaig et al.	356	601	09/13/02

FOREIGN PATENT DOCUMENTS

ĺ		DOCUMENT					TRANS	LATION
i	REF	Number	DATE	COUNTRY	CLASS	SUBCLASS	YES	No
ĺ	 AM	WO 03/009063	01/30/03	PCT	G03F	7/20		

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

	AN	J. Opsal et al., "Contact hole inspection by real-time optical CD metrology", Metrology, Inspection, and Process Control for
		Microlithography XVII, Daniel J. Herr, Editor, Proceedings of SPIE Vol. 5038 (2003), pp. 597-603.
	AO	J. Bischoff et al., "Optical Digital Profilometry applications on contact holes", Metrology, Inspection, and Process Control
		for Microlithography XVII, Daniel J. Herr, Editor, Proceedings of SPIE Vol. 5038 (2003), pp. 1080-1088.
	AP	B.D. Bunday et al., "CD-SEM Measurement of Line Edge Roughness Test Patterns for 193 nm Lithography", Metrology,
		Inspection, and Process Control for Microlithography XVII, Daniel J. Herr, Editor, Proceedings of SPIE Vol. 5038 (2003),
		pp. 674-688.

	Examiner	Date Considered			
١	·				
	Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if				
	not in conformance and not considered. Include copy of this form with next communication to applicant.				